

## Korean International Semiconductor Conference & Exhibition on Manufacturing Technology 2025

## **KISM 2025 BUSAN**

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

| [WeE2] Al-Driven CMP and Emerging Proce |
|---|
|---|

Session Date November 12 (Wed.), 2025

**Session Time** 14:10-15:40

Session Room Room E (Sicily Room, 1F)

[WeE2-1] [Invited] 14:10-14:40

Machine Learning-Based Strategic Corrosion Management for Targeted Inhibitor Implementation in CMP Applications

Jihoon Seo (Clarkson Univ., USA)

[WeE2-2] 14:40-15:00

Mechanism on Formation of Selective Hindrance Layer on Si-Film Enhancing Etch-Rate Selectivity of  $Si_{1-x}Gex$  to Si-Film

Chang-Jin Lee and Jea-Gun Park (Hanyang Univ., Korea)

[WeE2-3] 15:00-15:20

Design Rules for Micro-Structured Chemical Mechanical Polishing Pads to Enhance MRR Hyun Jun Ryu, Seounghee Yun, and Sanha Kim (KAIST, Korea)

[WeE2-4] [Invited] 15:20-15:40

Post CMP Cleaning Strategies for Amorphous Silicon in Wafer Bonding Processes

Arunkumar G V, Wei-Tsu Tseng, Nancy Wang, and Donald Canaperi (IBM Research, USA)